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U.S. DEPARTMENT OF COMMERCE  
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APPLICANT: PADMANABAN et al.

FILING DATE: 01/26/99

GROUP 1752

**OTPE JC19**  
**JUN 10 1999**  
**PATENT & TRADEMARK OFFICE**

U.S. PATENT DOCUMENTS

Examiner Initial		Patent Number	Issue Date	Patentee	Class	Subclass	Filing Date If Appropriate
RA	A	US 4370405	01/25/83	O'Toole et al.	430	312	
	B	US 4575480	03/11/86	Kotani et al.	430	192	
	C	US 4636431	01/13/87	DeBergalis	428	327	
	D	US 4882260	11/21/89	Kohara et al.	430	191	
	E	US 5093414	03/03/92	Rauterkus et al.	524	813	
	F	US 5234990	08/10/93	Flaim et al.	524	609	
RA	G	US 5294680	03/15/94	Knors et al.	524	327, GROUP 1752	
FOREIGN PATENT OR PUBLISHED FOREIGN PATENT APPLICATION							
		DOCUMENT NUMBER	PUB. DATE	COUNTRY			TRANSLATION
RA		EP 0542008	05/19/93	Europe			Yes
RA		EP 0583205	02/16/94	Europe			Yes

OTHER DOCUMENTS (Including Author, Title, Date, Place of Publication\*\*)

RA		"Antireflection Layers and Planarization for Microlithography," M. Horn, SOLID STATE TECHNOLOGY, Nov. 1991, pp. 57-62
RA		"Optimization of Optical Properties of Resist Processes," T. Brunner, Proc. SPIE, Vol. 1466, Advances in Resist Technology and Processing VIII (1991) pp. 297-307
RA		"One Micron Lithography Using A Dyed Resist On Highly Reflective Topography," M. Bolsen, G. Buhr, H.J. Merrem, K. vanWerden, SOLID STATE TECHNOLOGY, February 1986, pp. 83-88
RA		"High Contrast Single Layer Resists and Antireflection Layers - An Alternative to Multilayer Resist Techniques," C. Nölscher, L. Mader, M. Schneegans, Proc. SPIE Vol. 1086 Advances in Resist Technology and Processing VI (1989), pp. 242-250
RA		"Tin, O <sub>2</sub> As A Barrier Between Cr-Si-(O) And Aluminum Thin Films," K.H. Bäther and H. Schreiber, THIN SOLID FILMS, 200, 1991, pp. 93-116
RA		"Reduction Of Linewidth Variation For The Gate Conductor Level By Lithography Based On A New Antireflective Layer," G. Czech, L. Mader, K.H. Küsters, P. Küppers, and A. Gutmann, MICROELECTRIC ENGINEERING, 21, (1993) pp. 51-56
RA		"Two Anti-Reflective Coatings For Use Over Highly Reflective Topography," A.T. Jeffries, M. Toukhy and T.R. Sarubbi, Proc. SPIE, Vol. 539 Advances in Resist Technology and Processing II (1985), pp. 342-348
R		"Design Of A Bottom Anti-Reflective Layer For Optical Lithography," J. Fahey, W. Moreau, K. Welsh, S. Miura, N. Eib, and G. Spinillo, Proc. SPIE, Vol. 2195, pp. 422-433
EXAMINER <i>P. Ashman</i>		DATE CONSIDERED 7/27/00
EXAMINER: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.		